

Accession number:20120314695400

Title:Microfabrication of fine electron beam tunnels using UV-LIGA and embedded polymer monofilaments for vacuum electron devices

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Source title:Journal of Micromechanics and Microengineering

Abbreviated source title:J Micromech Microengineering

Volume:22

Issue:1

Issue date:January 2012

Publication year:2012

Article number:015010

Language:English

ISSN:09601317

E-ISSN:13616439

CODEN:JMMIEZ

Document type:Journal article (JA)

Publisher:Institute of Physics Publishing, Temple Circus, Temple Way, Bristol, BS1 6BE, United Kingdom

Abstract:Vacuum electron devices require electron beams to be transported through hollow channels that pass through an electromagnetic slow-wave circuit. These electron 'beam tunnels' are shrinking toward sizes smaller than traditional techniques can manage as the operating frequencies push toward the THz. A novel technique is described and experimentally demonstrated that uses polymer monofilaments of arbitrary cross-sectional shape combined with ultraviolet photolithography (UV-LIGA) of SU-8 photoresists. This combination of monofilaments and SU-8 structures comprises a 3D mold around which copper is electroformed to produce high-quality beam tunnels of arbitrary length and size along with the electromagnetic circuits. True round beam tunnels needed for upper-millimeter wave and THz vacuum electron devices can now be fabricated in a single UV-LIGA step. These techniques are also relevant to microfluidic devices and other applications requiring very small, straight channels with aspect ratios of several hundred or more. © 2012 IOP Publishing Ltd.

Number of references:26

Main heading:Electrons

Controlled terms:Aspect ratio - Electromagnetism - Electron beams - Electron devices - Millimeter wave devices - Photoresists - Terahertz waves - Vacuum

Uncontrolled terms:Beam tunnel - Cross-sectional shape - Electromagnetic circuits - High quality - Micro-fluidic devices - Novel techniques - Operating frequency - Other applications - Polymer monofilaments - Round beams - Slow wave circuits - Straight channel - SU-8 photoresist - SU-8 structure - Traditional techniques - Ultraviolet photolithography - UV LIGA - Vacuum electron devices

Classification code:932 High Energy Physics; Nuclear Physics; Plasma Physics - 741.1
Light/Optics - 715 Electronic Equipment, General Purpose and Industrial - 943 Mechanical and
Miscellaneous Measuring Instruments - 711 Electromagnetic Waves - 701 Electricity and
Magnetism - 633 Vacuum Technology - 701.1 Electricity: Basic Concepts and Phenomena

DOI:10.1088/0960-1317/22/1/015010

Database:Compendex

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